

# Ti-diffused LiNbO<sub>3</sub> optical waveguides with low loss

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The fabrication and performance of optical waveguides by the in-diffusion of titanium into LiNbO<sub>3</sub> were investigated. We employ a closed-tube diffusion system and a method to supply Li. The LiNbO<sub>3</sub> powder which has the same stoichiometry as the sample substrate and the Ti-sputtered LiNbO<sub>3</sub> wafer were placed in closed rectangular (77×23×21 mm<sup>3</sup>) white alundum boat. For most of the experiments, fresh LiNbO<sub>3</sub> powder (0.5g) was used each time. Titanium films were deposited onto y-cut LiNbO<sub>3</sub> substrates by RF sputtering from a high-purity (99.99%) titanium. Under the diffusion conditions of time (8hr) and temperature (1000°C), we have found that it is possible to obtain single-mode waveguides (at 6328 Å), for Ti-films ranging in thickness between 192 and 460 Å. The fabrication of waveguides is very simple and reproducible and it is possible both to suppress Li<sub>2</sub>O out-diffusion and to obtain the waveguides with low loss (~1 db/cm). Hence this technology is reasonable.

Under the conditions of suppressing Li<sub>2</sub>O out-diffusion, the characteristics and parameters of the optical waveguides (such as mode index  $n_m$ , maximum index change  $\Delta n_s$ , diffusion depth  $d$ , diffusion constant  $D$ ) have been measured and calculated by using the secant hyperbolic profile (zero order perturbation) and parabolic approximation respectively, which have not been reported yet.

## 低损耗 Ti 扩散 LiNbO<sub>3</sub> 光波导

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本文对钛内扩散 LiNbO<sub>3</sub> 光波导的制备和性能进行了研究。我们采用闭管扩散工艺和补 Li 措施, 密闭长方形(77×23×21 mm<sup>3</sup>) 白刚玉舟内放有与样品衬底相同化学配比的 LiNbO<sub>3</sub> 粉和溅射过 Ti 的 LiNbO<sub>3</sub> 片子, 多数实验每次用新的 LiNbO<sub>3</sub> 粉 0.5 克。由高频溅射高纯 (99.99%) 钛的办法, 在 y-切 LiNbO<sub>3</sub> 衬底上淀积钛膜, 在温度为 1000°C, 时间为八小时的扩散条件下发现, Ti 膜厚度在 192-460 Å 范围内, 可获得单模波导(6328 Å)。这种工艺使波导的制作十分简单, 重复性好, 而且既可抑制 Li<sub>2</sub>O 外扩散, 又可获得低损耗(~1 db/cm)光波导, 因此这种工艺是合理的。

在抑制 Li<sub>2</sub>O 外扩散的条件下, 分别用抛物线近似和双曲线正割分布(零级近似), 对光波导的特性和参数(如模折射率  $n_m$ 、最大折射率改变  $\Delta n_s$ 、扩散深度  $d$ 、扩散常数  $D$ ) 进行了测量和计算, 而这些还没有见过报导。